

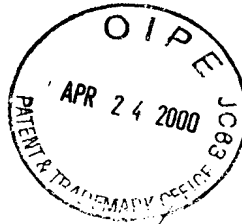
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Donald L. Yates

Serial No.: 09/123,430

Filed: July 28, 1998

For: METHOD OF REDUCING SURFACE
CONTAMINATION IN SEMICONDUCTOR
WET-PROCESSING VESSELS



Group Art Unit: 2823

Examiner: B. Kebede

Assistant Commissioner for Patents
Washington, D.C. 20231

AMENDMENT

Dear Sir:

This is a response to the Office Action dated January 24, 2000 (Paper No. 6).

Claims 1-17, 20-27 and 44 have been amended. A new oath/declaration has been submitted. Formal drawings have been filed concurrently.

IN THE CLAIMS:

Please amend the following claims:

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work

1. (amended) A method for removing contaminants from a semiconductor processing bath for processing semiconductor wafers, said method comprising:

rapidly removing an upper portion of a [the] semiconductor processing fluid present in said bath while said wafers are in said bath.

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